Title (en)

QUARTZ GLASS COMPONENT WITH REFLECTOR LAYER AND METHOD FOR PRODUCING THE SAME

Title (de)

QUARZGLAS-BAUTEIL MIT REFLEKTORSCHICHT SOWIE VERFAHREN ZUR HERSTELLUNG DESSELBEN

Title (fr)

COMPOSANT EN VERRE QUARTZEUX À COUCHE RÉFLÉCHISSANTE ET SON PROCÉDÉ DE FABRICATION

Publication

EP 2102125 A1 20090923 (DE)

Application

EP 07857521 A 20071213

Priority

- EP 2007063874 W 20071213
- DE 102006062166 A 20061222

Abstract (en)

[origin: US2009316268A1] Methods for producing a quartz glass component with reflector layer are known in which a reflector layer composed of quartz glass acting as a diffuse reflector is produced on at least part of the surface of a substrate body composed of quartz glass. In order, taking this as a departure point, to specify a method which enables cost-effective and reproducible production of uniform SiO2 reflector layers on quartz glass components, it is proposed according to the invention that the reflector layer is produced by thermal spraying by means of SiO2 particles being fed to an energy carrier, being incipiently melted or melted by means of said energy carrier and being deposited on the substrate body. In the case of a quartz glass component obtained according to the method, the SiO2 reflector layer is formed as a layer which is produced by thermal spraying and has an opaque effect and which is distinguished by freedom from cracks and uniformity.

IPC 8 full level

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CPC (source: EP KR US)

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Citation (search report)

See references of WO 2008077807A1

Citation (examination)

EP 1352986 A2 20031015 - TOSOH CORP [JP]

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US 2009316268 A1 20091224; **US 7947335 B2 20110524**; CN 101568497 A 20091028; CN 101568497 B 20121003; DE 102006062166 A1 20080626; DE 102006062166 B4 20090514; EP 2102125 A1 20090923; IL 198953 A0 20100217; IL 198953 A 20130627; JP 2010513198 A 20100430; JP 5432721 B2 20140305; KR 101111659 B1 20120214; KR 20090100372 A 20090923; WO 2008077807 A1 20080703

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